

ITW

Docket No.: SON-2811

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Kaoru Koike

Application No.: 10/526,359

Confirmation No.: 8957

Filed: October 18, 2005

Art Unit: 2825

For: ALIGNMENT METHOD, ALIGNMENT
SUBSTRATE, PRODUCTION METHOD OF
ALIGNMENT SUBSTRATE, EXPOSURE
METHOD, EXPOSURE APPARATUS AND
PRODUCTION METHOD OF MASK

Examiner: Stacey Whitmore

REQUEST FOR EXPRESS ABANDONMENT


MS Express Abandonment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Applicant through the undersigned attorney/agent of record hereby expressly
abandons the above-captioned application.

Dated: March 7, 2008

Respectfully submitted,

By 

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